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THE UNITED STATES PATENT AND TRADEMARK OFFICE
Applicant: Choi et al. PATENT APPLICATION
Serial No.: 09/698,317 Group Art Unit: 2859
Filing Date: October 27, 2000 Examiner: Unassigned
For: HIGH-PRECISION ORIENTATION ALIGNMENT AND GAP CONTROL STAGES
FOR IMPRINT LITHOGRAPHY PROCESSES

INFORMATION DISCLOSURE STATEMENT

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ISSUED PATENTS

| <u>Patent Number</u> | <u>Inventor</u> | <u>Grant Date</u> |
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FOREIGN PATENT DOCUMENTS

| <u>Document Number</u> | <u>Inventor</u> | <u>Pub. Date</u> |
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| WO 92/17883 | Olsson | Oct. 15, 1992 |
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NON-PATENT DOCUMENTS

Lin, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, NY 10598.

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Chou et al., "Imprint of Sub-25nm Vias and Trenches in Polymers", Applied Physics Letters, Nov. 20, 1995, pp. 3114-3116, vol. 67(21).

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Xia et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp.
550-575, vol. 37.

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Respectfully Submitted,

Kenneth C. Brooks

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| Filing Date | October 27, 2000 |
| First Named Inventor | Choi et al. |
| Group Art Unit | 2859 |
| Examiner Name | Unassigned |
| Attorney Docket Number | PA09-06V02 |

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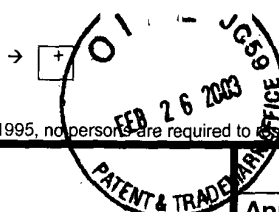
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| | | | First Named Inventor | Choi et al. |
| | | | Group Art Unit | 2859 |
| | | | Examiner Name | Unassigned |
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| OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS | | | |
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| Examiner Initials* | Cite No. | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
| | B10 | LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598. | |
| | B11 | COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291. | |
| | B12 | CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21). | |
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